

COLUMBIA UNIVERSITY IN THE CITY OF NEW YORK COLUMBIA NANO INITIATIVE / CENTER FOR INTEGRATED SCIENCE AND ENGINEERING

OXFORD ICP PlasmaLab 80+



These instructions are intended for reference only, and will *not* replace the thorough training required for proper system operation. The procedure is written for operating the tool in **automatic mode**. Contact a clean room staff member with questions or to report a system problem.

Written by: James Vichiconti





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| 3. | VERIFY SYSTEM STATUS | E Batch ID |
|----|--|---|
| | The system should be left | columbia Brecipe |
| | 'pumped down' and clean | Cumber dass -Rubic v V Cumber dass -Rubic v |
| | (Chamber Clean recipe) to | KO HI SI |
| | maintain chamber | Wat |
| | integrity. Please note the | Pumped down |
| | green wafer which | |
| | indicates the 'Chamber | Proces |
| | Clean' process has been | Rung Vert |
| | completed. | O schedular Job colamba Hile |
| | If the wafer is not 'green' | 202142 |
| | and the Chamber Clean | 1)) Jagazes 💩 Thursday (OXEORD |
| | recipe is not indicated, | |
| | please report the condition | |
| | in Badger and run a | |
| | in Baager and ran a | |
| | chamber clean prior to | |
| | chamber clean prior to process you samples. | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page click 'vent'. | |
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| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page click 'vent'. The vent process takes several minutes, because it initiates system pump down and a nitrogen purge | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page click 'vent'. The vent process takes several minutes, because it initiates system pump down and a nitrogen purge cycle before the chamber | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page click 'vent'. The vent process takes several minutes, because it initiates system pump down and a nitrogen purge cycle before the chamber is brought to atmospheric | |
| 4. | chamber clean prior to process you samples. VENT THE SYSTEM On the 'Automatic' page click 'vent'. The vent process takes several minutes, because it initiates system pump down and a nitrogen purge cycle before the chamber is brought to atmospheric pressure, to assure that | |





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| | gases have been cleared from the chamber. | <image/> |
|----|---|----------|
| 5. | INSTALL SAMPLE When the chamber is fully vented, open the chamber using the pneumatic controls. For samples that require thermal conductivity with the base plate, coat the backside of the sample with a thin film of Fomblin oil or Cool Grease, taking care to cover the entire surface. Place your sample at the center of the chamber's base plate. | |



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| 6. | Evacuate Chamber Answer "yes" to the "wafer loaded in to the chamber" question. There is a fixed wafer mounted at all times. Under the "Process" header, select "Pump". | In Cross The Cose Maximum Maximum Ma Maximum Maximum |
|----|--|---|
| 7. | DEFINE PROCESS Select your recipe and load. You will need to enter a batch ID as well. | Batch ID Columbia Docine Chamber Clean Chamber Clean Chamb |
| 8. | RUN PROCESS Select 'Run' to initiate the process. Note the cream color wafer graphic indicating the wafer has not been processed | Image: Sector |



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| | wafer using a clean room | |
|-----|-------------------------------|---|
| | wipe and DI water. Dry the | |
| | platen. As a reminder IPA | |
| | use outside of the litho | |
| | hoods is not allowed (it | |
| | triggers the gas sensors). | |
| 12. | RETURN TO NORMAL | |
| | Leave the tool as you | Batch ID |
| | found it by closing the lid | E Columbia |
| | using the pneumatic | SET |
| | controls and initiating the | Chamber Clean |
| | vacuum cycle. | Chamber Clean -Admin |
| | | gas on OPT – Si Etch |
| | Run a post process | OPT - Si Etch - Admin |
| | chamber clean. | DPT - Sij Bich - Ox Test |
| | | |
| 13. | BADGER LOGOUT: Don't | CNI (np2496@columbia.edu) Badger Window Equipment Actions Reservation Actions History Actions Enable CNI |
| | forget to disable the tool in | Control Contro Control Control Control Control Control Control Control Control Co |
| | badger after you're done. | Qualify Userstor* Browse Manualch* @ Edwards Thermal Evaporator 1* @ Edwards Therma Evaporator 1* |
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